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TC 1700

AT/1752
PATENT
30205/37328

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of: Min Ho Jung et al.

Serial No.: 09/878,803

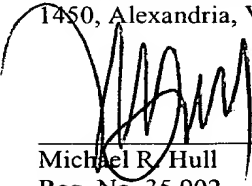
Filed: June 11, 2001

For: Additive for Photoresist
Composition for Resist Flow Process

Group Art Unit: 1752

Examiner: Yvette C. Thornton

) I hereby certify that this paper and the
) documents referred to as enclosed
) therewith are being deposited with the
) United States Postal Service as first class
) mail, postage prepaid, on **December 18,**
) **2003**, in an envelope addressed to
) Commissioner for Patents, P.O. Box
) 1450, Alexandria, Virginia 22313-1450

) 
) Michael R. Hull
) Reg. No. 35,902
) Attorney for Applicants
)

AMENDMENT AFTER FINAL (37 C.F.R. § 1.116)

Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

Please enter the following amendment in the above-referenced patent application.